

# GaN-on-Silicon for 5G Radios

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International Microelectronics  
Assembly and Packaging Society

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- > Introduction to 5G
  - Why 5G
  - 3G to 4G to 5G Transition
  - Frequencies – Microwave & mmW
- > Impact on Device Technologies
  - 4G Incumbent - LDMOS/GaN
  - 5G Future – GaN/GaAs/Silicon CMOS/SiGe & Massive MIMO Implications
  - RF System Operating Voltage & Technology Impact
- > GaN Revolution for 5G
  - Market vs Price
  - GaN-on-Silicon vs GaN-on SiC
  - Supply Chain
- > Future Expectations/Possibilities

# **Introduction to 5G**

**3G -> 4G -> 5G Transitions**

- Faster Data Rates
- Internet Connectivity
- Lower Latency
- Video
- Robotics
- Automotive
- Medical/Emergency Services
- All Require Substantial Increase in Bandwidth => Higher Frequencies

## > 3G/4G Systems

- Silicon LDMOS has been Incumbent Technology
- Historical Operating Voltage – 50 volts
- GaN has been Eroding Market Share Since 2015

## > 4G Dominated by Macro Base Stations

- Internally Matched Transistors in a Doherty Configuration
- Operating Voltage – 50 volts Minimum
- Final Stage Power Levels: 000's of Watts
- Majority of applications 2.6 GHz and below
- Very High Volume LDMOS Bands: 900MHz / 1800 MHz
- GaN Making Significant Market Penetration

## > 5G Sub-6GHz

- Initial Roll-Out - Higher Frequency Version of 4G
- Device Requirement - Tens to Hundreds of Watts
- 3.5 GHz – 4.9 GHz Bands Will be Populated First
- Antenna Technology – Massive MIMO Arrays
- Longer Term – mmW Bands – 28 GHz, 39 GHz, 60 GHz
- Operating Voltage – Function of Frequency - 50 volts -> 40 volts -> 28 volts
- Maximize Overall System Efficiency
- LMOS Cannot Meet Frequency Response at >24 volts
- GaAs – Limited to  $\approx 10$  volt Operation
- GaN is the ONLY Device Technology Choice

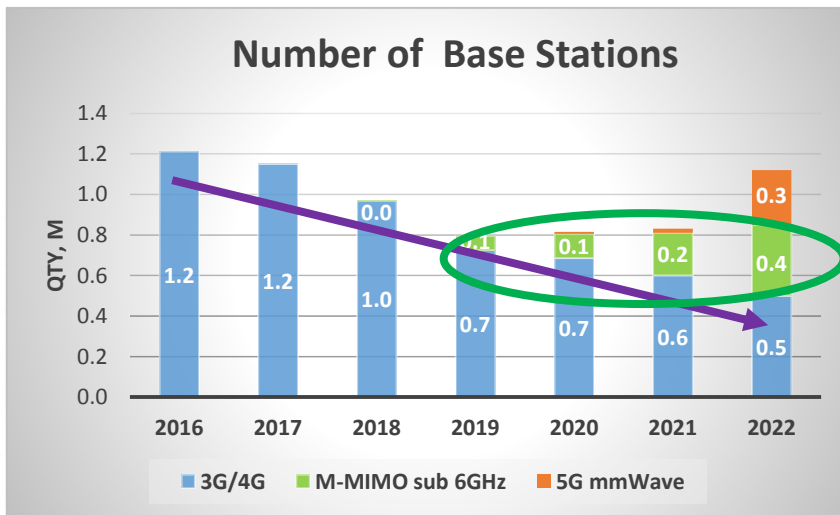
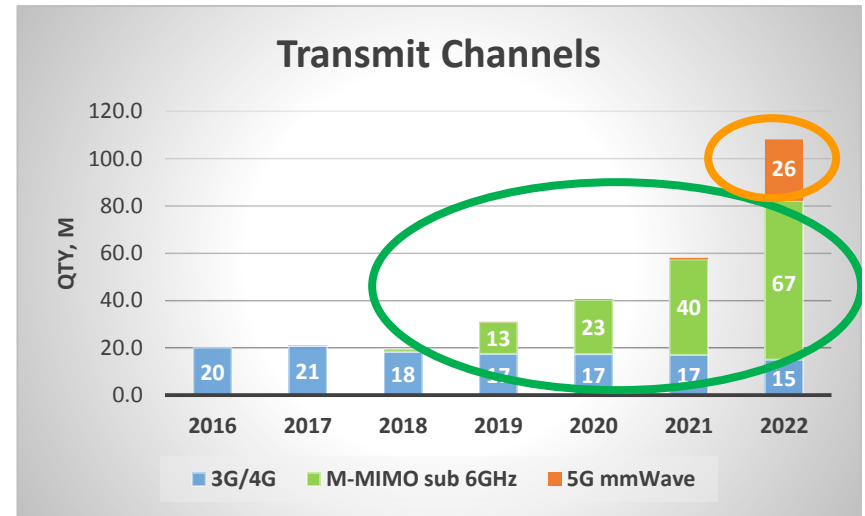
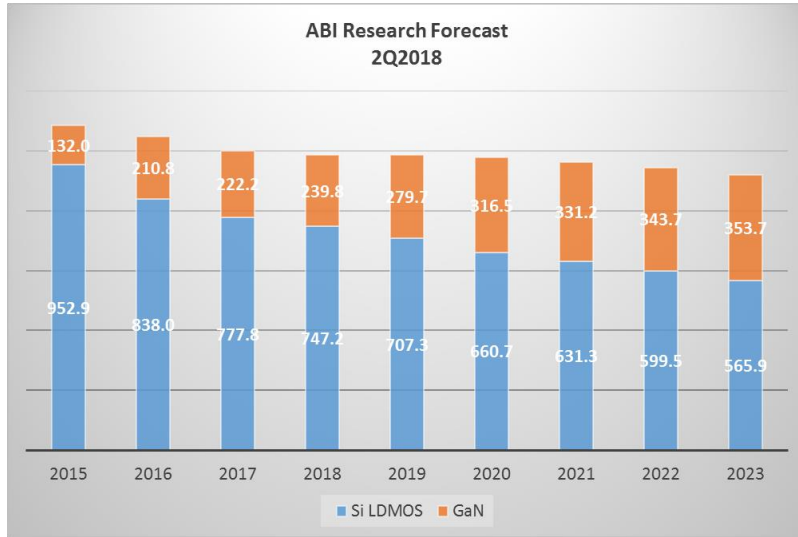
- 5G Moving to MIMO Antenna Configurations (from 2x2 to 8x8 and bigger)
  - Looks/Functions like a Phased Array Radar
  - Higher Frequencies/More Bandwidth
  - Power levels are dropping:  $P_{avg} \sim 5-10W$  –  $P_{peak} \sim 40 - 50W$
  - Multistage Device (“MMIC”) – Integrated Driver and Final Stage
  - Approaches: (1) True MMIC, (2) MMIC + Output IPD, (3) Hybrid Construction
  - Output Stage is still Doherty configuration
  - Packaging: QFN and Laminate
  - MMIC Volume and TAM (\$) will exceed Discrete Transistors significantly

## > mmW

- 28 GHz/39 GHz (Ka Band)
  - Multi-Beam Phase Shift Base Station Sites – MIMO/Pico Cells
  - System Efficiency => Higher Operating Voltages
  - PA Output Power Significantly Reduced – Few Watts
  - MMICs
  - Lower Voltage – 15 volts-28 volts? – Increase  $f_T$
  - SAT Comm/DBS Adjunctcicy Issue
  - Open Frequency Allocations
  - LDMOS Eliminated at these Frequencies
  - GaAs Possible Competitor – Requires Significant Voltage Reduction
- 60 GHz (V Band)
  - Multi-Beam Phase Shift Base Station Sites – MIMO
  - PA Output Power Significantly Reduced –  $\ll$  1 Watt
  - Low Operating Voltage
  - Open Frequency Allocation
  - SiGe/BiCMOS MMICs
  - Integrate Control Circuitry



# A Transistor Market or MMIC Market?



- GaN based devices will continue to grow taking market share from LDMOS
- Device volume growth will be in “MMIC’s” both for sub-6 GHz and mmW
  - PA can be just a sub-component of TRx FEM
- # of Basestation is flat – BUT - device quantity increases – m-MIMO Arrays drive quantity
  - Device technology must support shift in antenna architecture

# Massive MIMO Implications

# Why MMICs

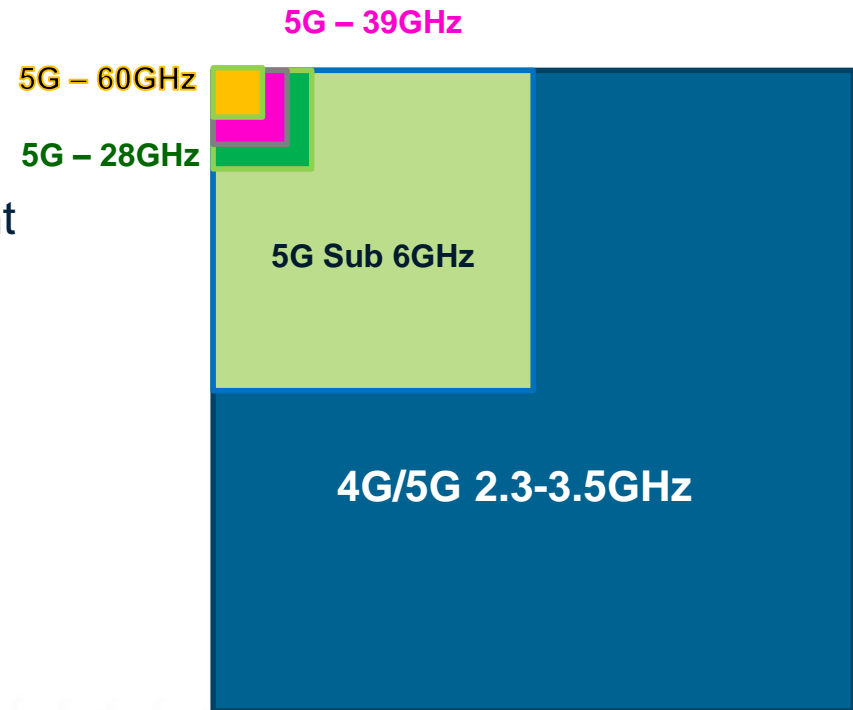
## MIMO Planar Antenna Arrays

- Similar Concept To Phased Array Radar
- Enables Steerable Transmission Beams
- 2x2 to 8x8 Element Arrays
- Array Size Dictated by Radiating Element Spacing –  $\lambda/2$

- Scales Directly with Frequency

- 2.3 GHz – 6.5 cm } 4G
- 3.5 GHz – 4.28 cm } Sub 6GHz 5G
- 4.9 GHz – 3.06 cm } Sub 6GHz 5G
- 28 GHz – 0.53 cm → mmW 5G
- 39 GHz – 0.38 cm → mmW 5G
- 60 GHz – 0.25 cm → mmW 5G

- Element Power Must Drop to Maintain Reasonable Array Temperatures
- Individual TR MMIC/Module Must Fit within the Horizontal Array Spacing
- MMIC Integration is Key - Esp mmW Solutions



Relative Array Size  
for an NxN Planar Array

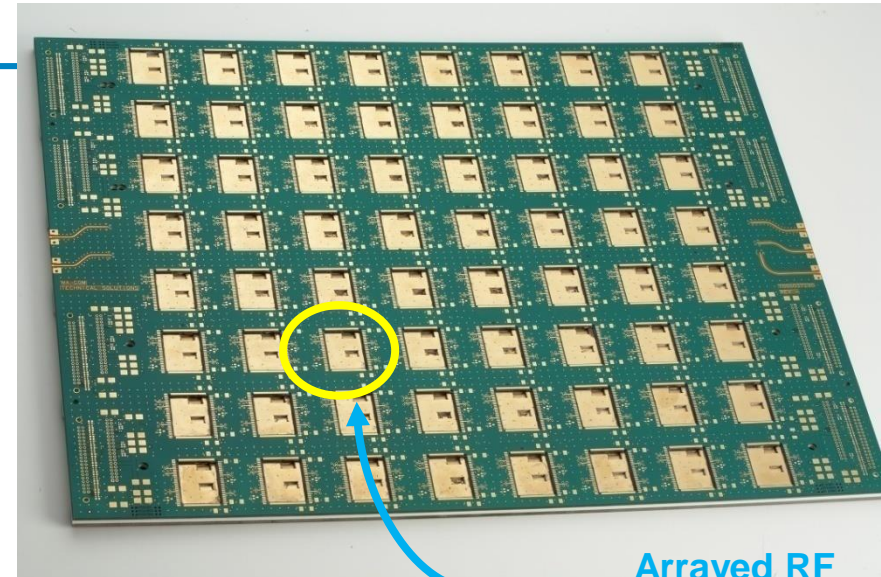
# T/R Module

## > Radiating Element Spacing

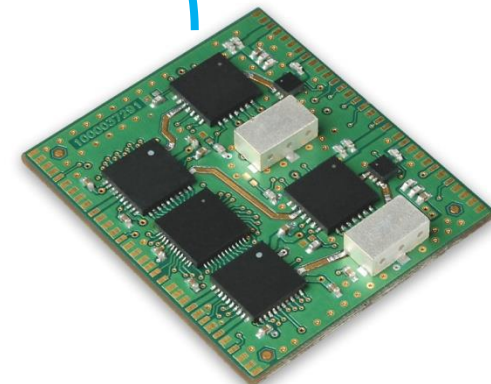
- $\lambda/2$
- S-Band =>  $\lambda/2 \approx 5$  cm
- Relatively Large Array Spacing
  - Simplifies T/R Module Realization
  - Custom MMICs Individually Plastic Packaged
  - Modular PCB Integration

## > T/R Module Concept

- Overall Dimensions -  $\approx 3.0$  cm x  $3.5$  cm
- Easily Fits into Required Array Spacing
- Land Grid Array
- Solder Tab I/O
- PCB - Five Layer Design
- Includes All DC, RF and Control Signal Routing
- Solder Reflow Insertion onto RF “Mother-board”
- Approach Applies Directly to Lower Frequencies



Arrayed RF  
“Mother-board”



T/R Module

# Why MMICs for mmW MIMO

## Typical Transmit/Receive MMICs/Module

### > Transmit

- Phase Shifter
- Pre-Driver/Driver Amplifier
- Attenuator

### > HPA

- Final Transmit Power to Radiating Elements

### > Receive

- Phase Shifter
- LNA
- Limiter
- Attenuator
- Band Pass Filter

### > Common Leg Circuit Concepts

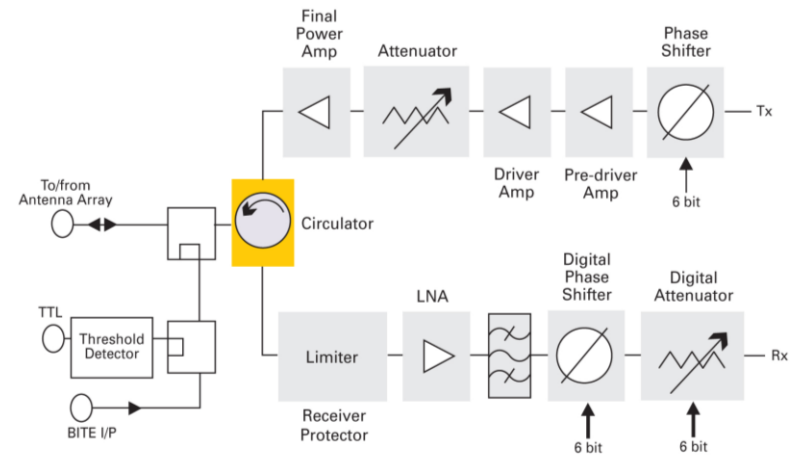
- Enables Phase Shifter/Attenuator to be Utilized in Both  $T_x$  and  $R_x$

### > Isolation

- Circulator/High Power/Isolation Switch
- SPDT Switch

### > Control Circuitry

- Digital Control in CMOS
- Converts Serial Bit Stream for  $T_x$  and  $R_x$  Phase & Attenuation to Parallel Outputs
- Control Capability to Determine Transmit State



**Basic RF Transmit/Receive Module  
Block Diagram**

# GaN Revolution for 5G

- Only GaN-on-Silicon/GaN-on-Silicon MMICs at 5G Frequencies Can Meet ALL the Performance/Supply Chain Challenges
- Market vs Price
- GaN-on-Silicon vs GaN-on SiC
- New Rules/Challenges
- Supply Chain
- Future Expectations/Possibilities

# The 5G GaN Revolution

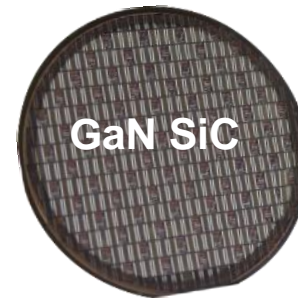
## > Driving GaN to Mainstream Commercial Adoption

### > GaN-on-SiC

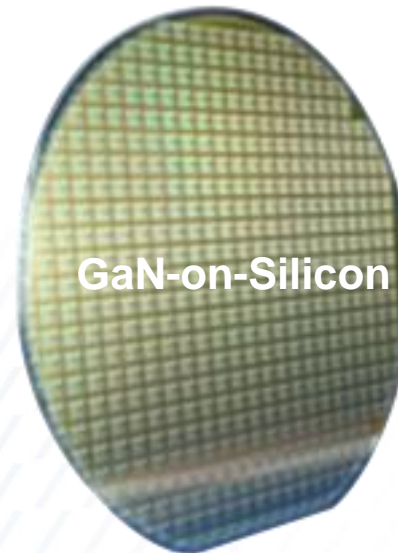
- Small Diameters
- Small, Boutique FABs
- Limited Ability to Scale

### > GaN-on-Silicon

- Large Wafer Diameters
- Leverage High Volume Silicon
  - Processing Capability/Discipline
  - Supply Chain Robustness
  - Cost Structure
- Path to Full CMOS Silicon Integration



Small Wafers – Small FABs



Large Wafers – High Volume FABs



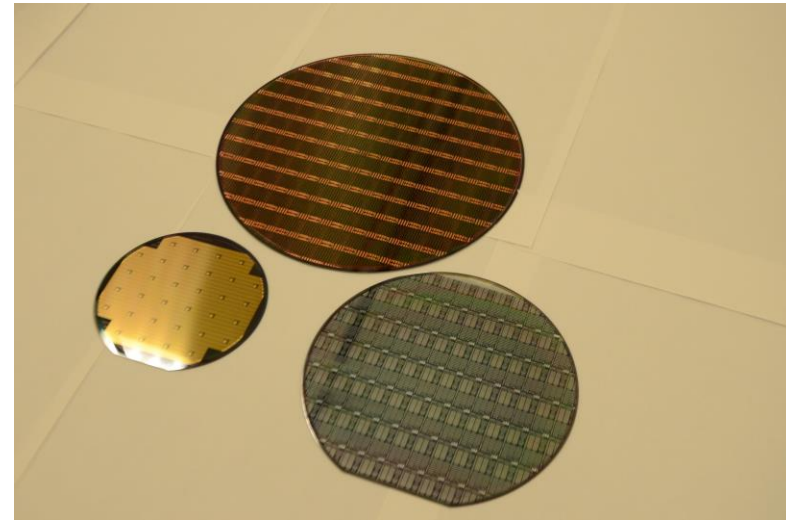
GaN Must Compete on BOTH Cost and Performance to Win in the Market!!

**GaN Performance at LDMOS Prices!!**



# Motivation for GaN-on-Silicon Industrialization

- > Market Opportunities – Everything Begins Here
- > Price Drives Volume – Volume Drives Cost
- > High Volume MOSFET Silicon Fab
- > Volume Capabilities of Typical CMOS Fab
  - Thousands of Wafers/Week
  - Wafer Diameter – 150mm (6”) -> 200mm (8”) -> 300mm (12”)
  - Cycle Times
    - Many Mask/Process Steps per Week
    - Provides Surge Capacity – Smooth Out Market Fluctuations
- > Price/Cost Drivers
  - GaN/Si – Existing Silicon Volume Spreads Overhead Costs
  - Large Wafer Diameters – 2.25x/4x/9x Increases in Die Count
  - High Line Yield



100mm – 150mm – 200mm GaN/Si Wafers

# The Market Sets the Price

Market	Typical Device	Price Point
Aerospace and Defense	Broadband, High Efficiency, MMIC HPA • 10 – 1000 W • 28/48 V operation	\$2.00 – \$5.00/Watt
CATV	Low Frequency, Broadband, High Linearity	\$0.5 – \$1.00
Infrastructure	Discrete Power Transistors	\$0.15 – \$0.30/Watt

- > The lowest cost solution ***always*** wins in the marketplace
- > So .... If Silicon can do .... Silicon will win ....
- > So .... If Silicon can't & GaAs can .... GaAs will win ....
- > GaN needs to provide unique solutions & provide compelling value to win

# Silicon vs. SiC Wafer Substrate Production



**Silicon Ingot**  
(6" wafer = \$20)

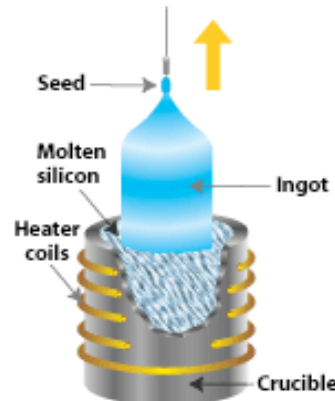


Illustration courtesy of EERE & U.S. Dept. of Energy

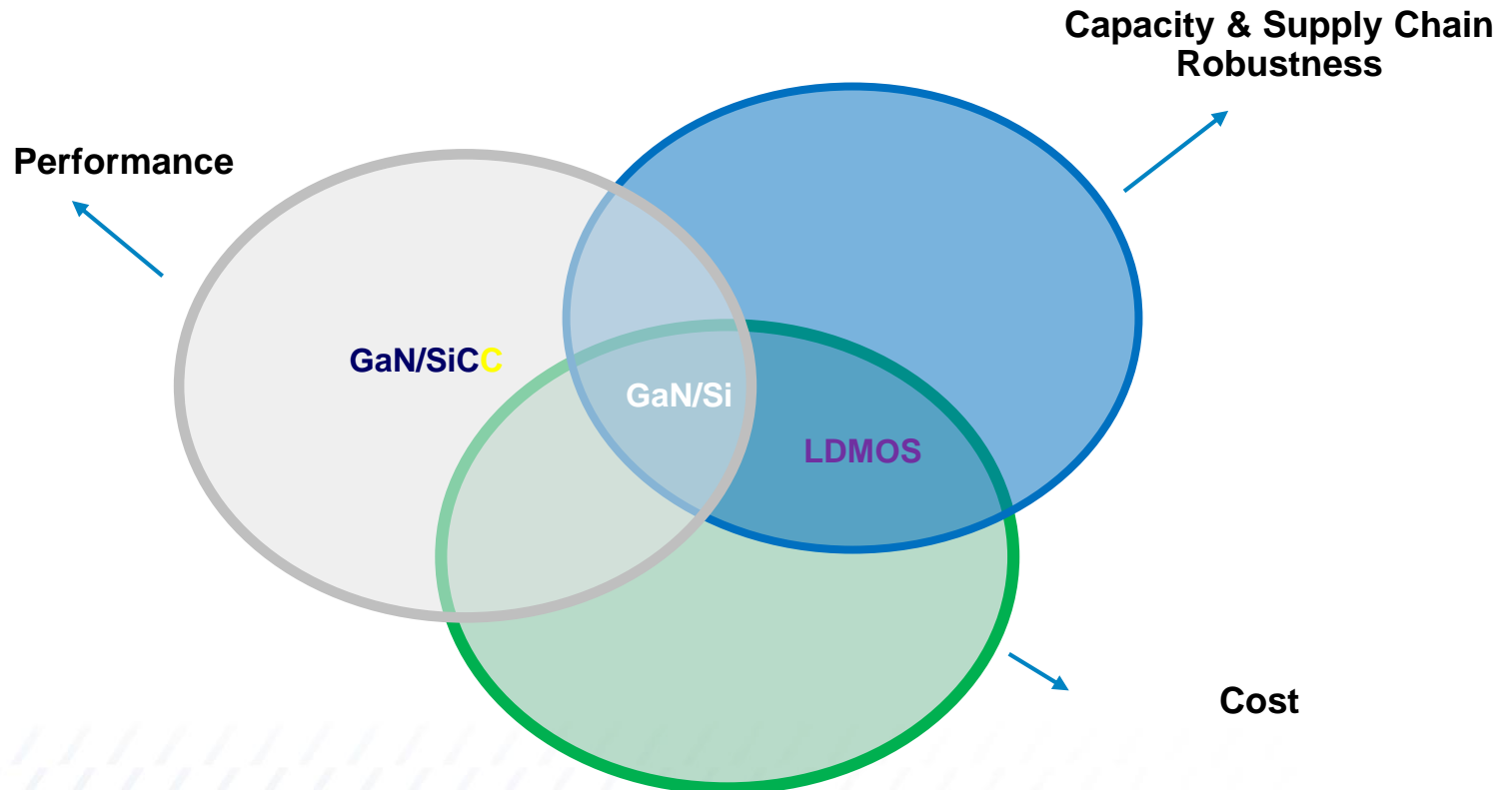
**Silicon Ingot Pulling**  
 $\approx 1400^\circ\text{C}$   
 $> 3$  inches/hr

**SiC Ingot (6" wafer = \$6000)**



**High Temperature ( $> 2000^\circ\text{C}$ )**  
**PVT SiC Ingot Growth Reactor**  
 $100\mu\text{m/hr} - 200\mu\text{m/hr}$

**3000 Si wafers from a single ingot vs.  $< 100$  SiC wafers from a SiC "ingot"**



## GaN/Si

Offers the Best of All Requirements

Performance

Cost

Scalability

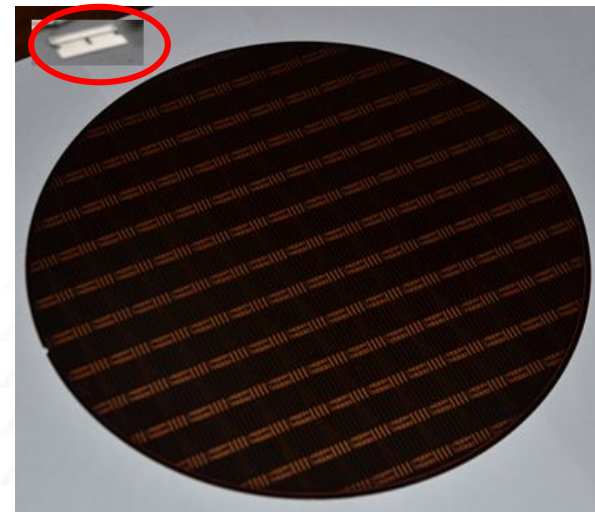
Supply Chain Robustness

# GaN Future Directions

- > Happening NOW!!
- > GaN-on-Silicon - Integrated in Large Diameter, High Volume, Silicon Fab
  - Needs “Large” Silicon Fab Partners
  - “Large” = 150mm/200mm Diameter 3000 – 15,000 wfs/wk
- > Process Must Adapt
  - Gold Free Processing – Aluminum/Copper Based Metallization
  - Dielectric Crossovers
  - Deep UV Steppers
  - Hands Off, Cassette-to-Cassette Processing
  - NO Recycles – Process Must Work First Time/Every Time



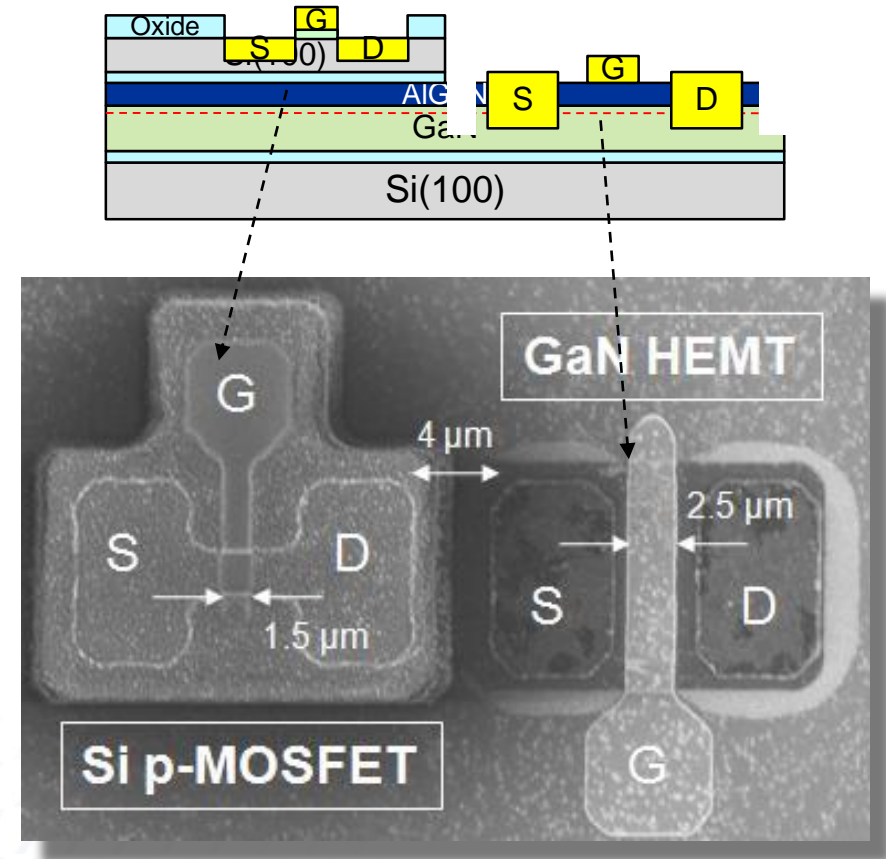
150 mm (6 inch) GaN/Si wafer (Power MOS Fab) with HF/RF/ $\mu$ W HEMT Devices



200 mm (8 inch) GaN/Si wafer (CMOS Fab) with HF/RF HEMT Devices

## > GaN/MOSFET Integration

- Integration of III-V HEMTs and Si (100) MOSFETs
- High power digital-to-analog converters (DACs)
- On-wafer wireless transmitters
- Driver stages for on-wafer optoelectronics
- Power amplifiers coupled to Si linearizer circuits
- High speed (high power) differential amplifiers
- Normally-off power transistors
- New enhancement-mode power transistors
- Buffer stages for ultra-low-power electronics



# Conclusions

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**Silicon is the MOST Mature, Defect-Free, Lowest Cost Substrate for Solid State Applications**

**Only GaN/Si can be Scaled to  $\geq 200\text{mm}$  Wafer Fabs & Meet the Volume Ramp Requirements for BTS and RFE Market Adoption**

**GaN/Si A&D Devices have Demonstrated Similar/Superior Performance to Equivalent GaN/SiC Devices**

**GaN/Si RFE Devices have Demonstrated Superior Efficiency, PAE Flatness, with Virtually Identical Output Power and Gain to LDMOS devices**

**GaN/Si Uniquely Enables Homogeneous Integration with CMOS**



**GaN/Si is Ideally Suited to Service Volume/Basestation RF Markets**